

METHOD OF PROCESSING SUBSTRATE, METHOD OF MANUFACTURING
SEMICONDUCTOR DEVICE, SUBSTRATE PROCESSING APPARATUS, AND
PROGRAM

ABSTRACT

The purpose of the present invention is to provide a technology capable of improving the step coverage of a film formed on a substrate. The present invention includes a supply step for supplying a processing gas to a substrate from a storage part in which the processing gas is stored. The supply step is carried out such that the amount of gas in the storage part when the supply step has ended is at or above a prescribed amount.

Fig. 6